



**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re the Application of: **Miwa KOZAWA et al.**

Group Art Unit: **1756**

Application Number: **10/670,291**

Examiner: **Daborah Chacko-Davis**

Filed: **September 26, 2003**

Confirmation No.: **6427**

For: **RESIST PATTERN THICKENING MATERIAL, PROCESS FOR  
FORMING RESIST PATTERN, AND PROCESS FOR  
MANUFACTURING SEMICONDUCTOR DEVICE**

Attorney Docket Number: **031181**

Customer Number: **38834**

**AMENDMENT**

Commissioner for Patents  
P. O. Box 1450  
Alexandria, VA 22313-1450

August 21, 2007

Sir:

This paper is filed in response to the Office Action dated March 21, 2007.

Amendments to the Claims begin on page 2 of this paper.

Remarks begin on page 7 of this paper.